Willkommen Welcome Bienvenue



Devastative contamination on DUV Laser mirrors and dreams for laser processing

Patrik Hoffmann

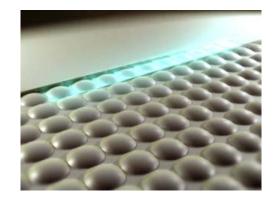
Laboratory for Advanced Materials Processing

Feuerwerkerstrasse 39 3602 Thun

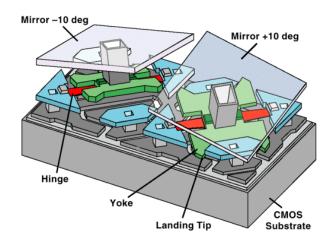
Outline



- Laser Materials processing by mask projection direct ablation
 - Excimer laser ablation on 3 m² substrate



- Dream of DUV micro mirror array
 - DLP® Products & MEMS



Full process for large surface microstructures



From Idea to CAD

Master substrate

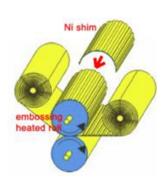
Metal copy Ni shim Production tools

Roll to roll embossing











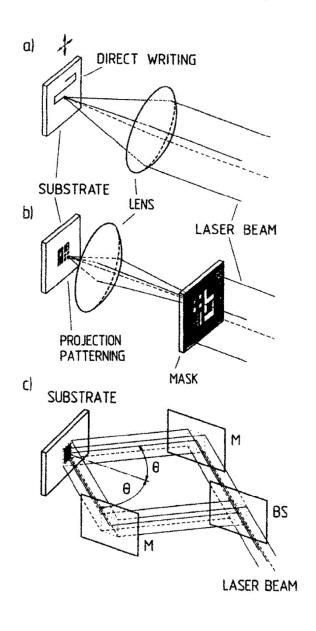
From requirements to origination to mass production

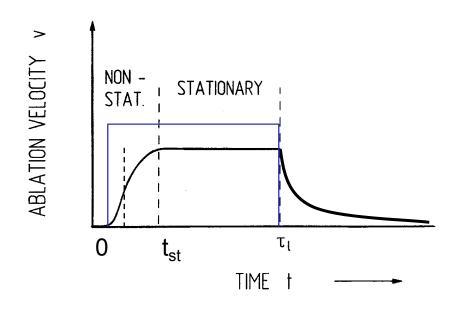
Empa and its partners can offer you all the steps from design up to roll to roll production.

use mold for other materials – ceramics, glasses,

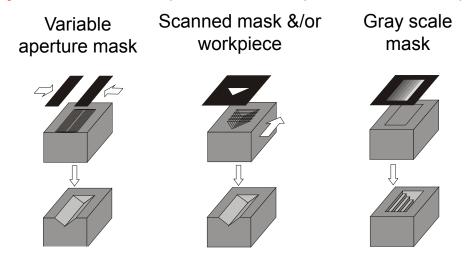
Laser materials processing: patterning







Projection ablation options for complex surface shapes



Ablation through the Graded Mask



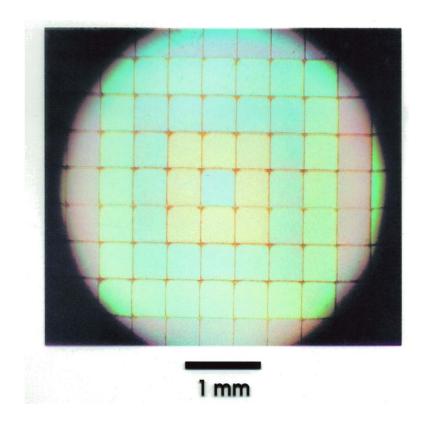
Graded Mask

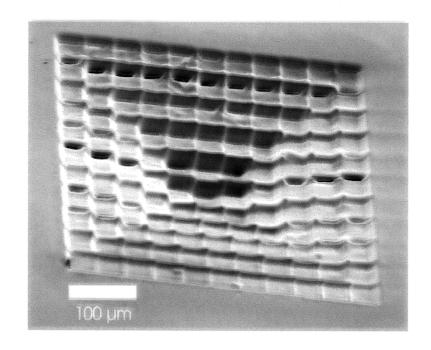
Material: HfO₂/SiO₂ on fused silica

Material: Polycarbonate

Laser 248 nm, 960 mJ/cm² (average),

100 pulse

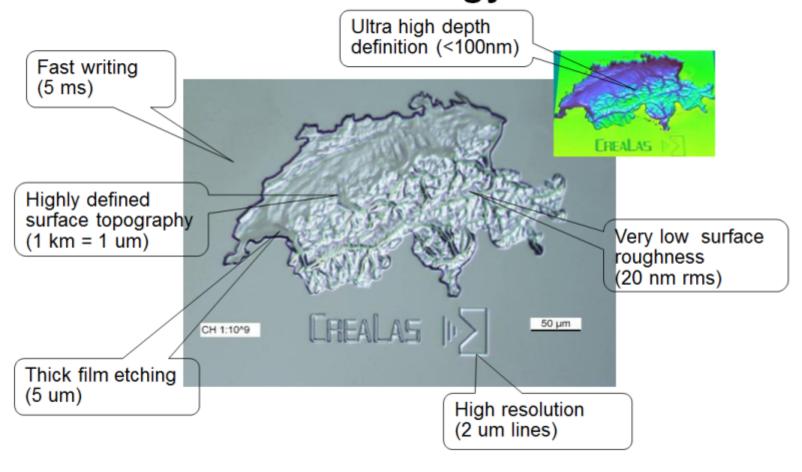




Laser-Laboratorium Göttingen e.V.



Technology:

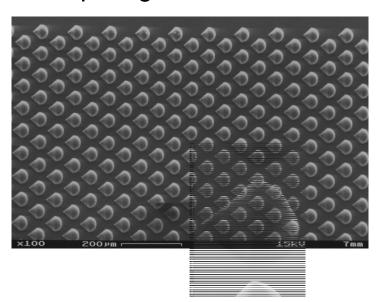


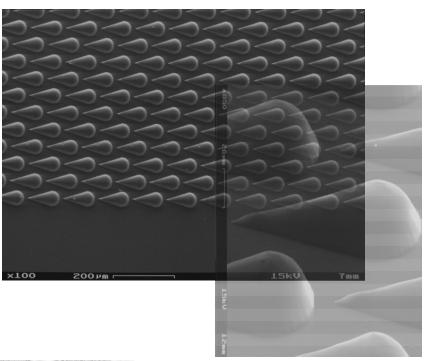


Product

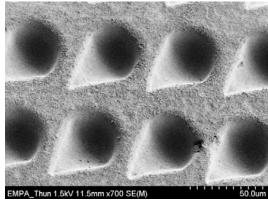


 Tear drop structures with variation of tear drop lenght and obstacle density





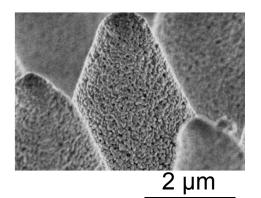
Replication in alumina nanoceramics



Few applications

EMPA (in Materials Science & Technology

1 Wetting

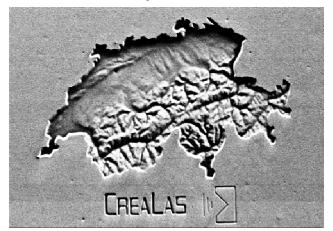




Superhydrophobic!!

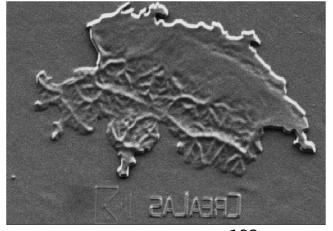
2 Ceramics as permanent molds

Alumina as permanent mold



100 μm

Replicated in PDMS from Alumina



100 µm

Further activities

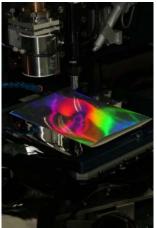
- Metal casting
- Polymer hot embossing

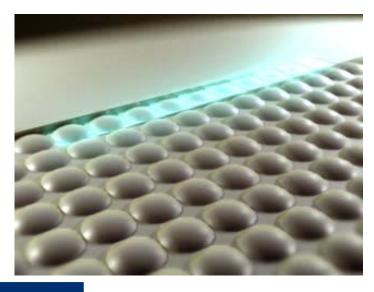
Rapid master fabrication



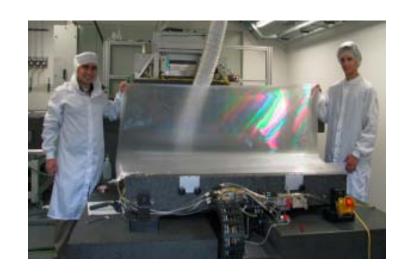


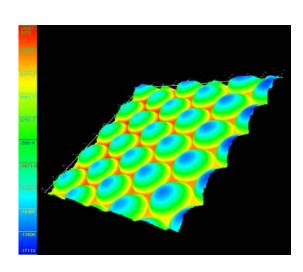






Three Systems worldwide, one running @ Empa in Thun !!

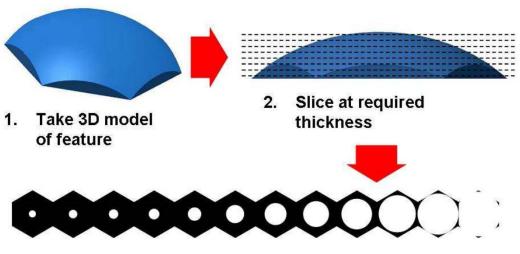




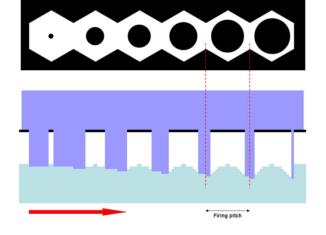
Laser cut Microlens array DHM measured $= 70 \mu m,$ $h = 25 \mu m$

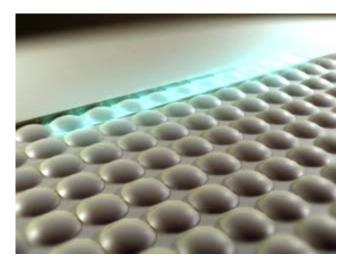
Synchronized Image Scanning (SIS)







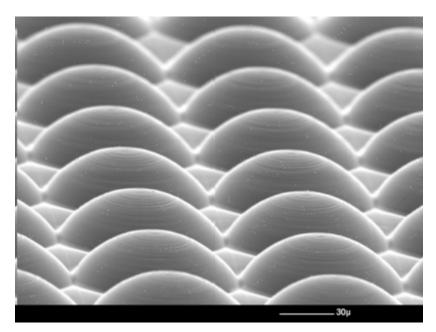


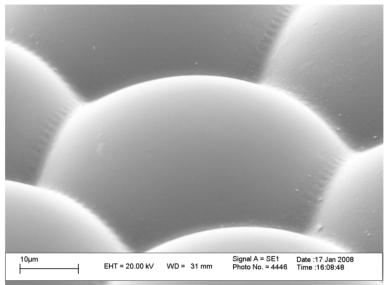


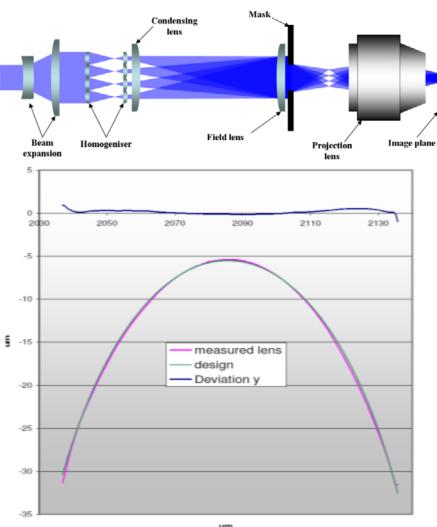


Feature quality: fit of target shape







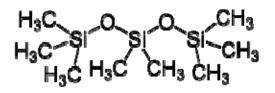


The average deviation from the best fit ROC is 147 nm with a ROC of 59.2 μ m while the target is 60 μ m.

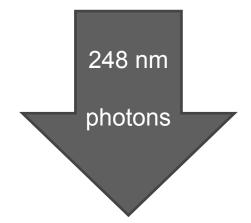
The problem: large surface machining – small but irreversible, irregular loss of light intensity











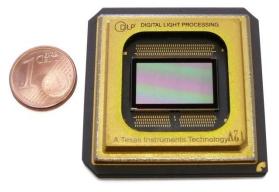
SiO₂:C

Dream for laser processing:

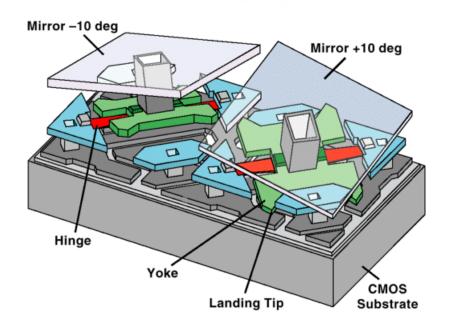
Materials Science & Technology

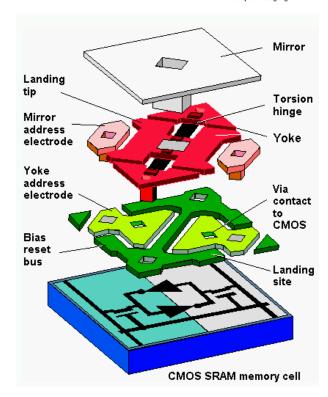
DUV Digital Light Processing @ 248nm





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How to do?



- Condense vapor on cover glass (liq. N₂)
- Remove cover glass
- Recover volatile liquid from glass
- Carry out two angles 248 nm HR coating on mirrors
- Condense vapor on chip (liq. N₂)
- Cover with 248nm AR coated fused silica or sapphire and hermetically seal cover

Who shares the risk with us?